

	Hits	Search Text	DBs
18	28	(mask\$3 or photomask or reticle) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or depress\$4 or touch\$3 or indent\$6) same (sample or substrate or wafer or photosensitive)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((immersion near6 lens) or (lens near5 element) or (refractive near22 slab)) and ((Maxwell near9 equation) or (proximity near9 correct\$4) or (thin near6 film near6 optics))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
19	13	((layout near8 object) or pattern\$4) same (mask\$3 or photomask or reticle)) and ((project\$4 near9 lens) same ((close near9 proximit\$4) or contact or vicinit\$3 or depress\$4 or touch\$3 or indent\$\$) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample) same ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
20	7	(mask\$3 or photomask or reticle) and ((project\$4 near9 lens)) and (((final or bottom) near5 lens near6 element) same ((close near9 proximit\$4) or distance or adjacent) same (sample or substrate or wafer or photosensitive or photoresist or resist)) and (expos\$4 or illuminant\$4 or irradiat\$4 or imag\$3) and ((lens or (refractive near26 slab) or (projection near6 lens near6 element)) same (adjacent or (close near6 proximit\$5) or abutt\$5) same (wafer or photoresist or substrate or photosensitive or sample) same ((refractive near6 index) or (index near4 refraction)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB